

IN THE DRAWINGS:

Please amend the drawings as shown in the attached figures in red.

IN THE CLAIMS:

Please amend the claims as follows:

1. (Twice Amended) A method of fabricating a display device comprising the steps of:
 - forming a semiconductor film over a substrate;
 - forming a gate insulating film on the semiconductor film;
 - forming a gate wiring on the gate insulating film;
 - forming a first organic leveling film over the gate wiring;
 - forming a second organic leveling film on the first organic leveling film; and
 - forming a pixel electrode on the second organic leveling film,
wherein the thickness of the first organic leveling film is thinner than that of the second organic leveling film.

2. (Twice Amended) A method of fabricating a display device comprising the steps of:
 - forming a semiconductor film over a substrate;
 - forming a gate insulating film on the semiconductor film;
 - forming a gate wiring on the gate insulating film;
 - forming a first organic leveling film over the gate wiring;
 - forming a second organic leveling film on the first organic leveling film; and
 - forming a pixel electrode on the second organic leveling film,

wherein the thickness of the first organic leveling film is thinner than that of the second organic leveling film and

wherein the thickness of the first organic leveling film is 0.1 μm or more and less than 1.5 μm .

3. (Twice Amended) A method of fabricating a display device comprising the steps of:

forming a semiconductor film over a substrate;

forming a gate insulating film on the semiconductor film;

forming a gate wiring on the gate insulating film;

forming a first organic leveling film over the gate wiring;

forming a second organic leveling film on the first organic leveling film; and

forming a pixel electrode on the second organic leveling film,

wherein the thickness of the first organic leveling film is thinner than that of the second organic leveling film, and

wherein the thickness of the second organic leveling film is from 0.1 μm to 2.9 μm inclusive.

4. (Twice Amended) A method of fabricating a display device comprising the steps of:

forming a semiconductor film over a substrate;

forming a gate insulating film on the semiconductor film;

forming a gate wiring on the gate insulating film;

forming a first organic leveling film over the gate wiring;

forming a second organic leveling film on the first organic leveling film; and

forming a pixel electrode on the second organic leveling film,

wherein the thickness of the first organic leveling film is thinner than that of the second organic leveling film, and

wherein the total thickness of the first organic leveling film and the second organic leveling film is from 0.2 μm to 3.0 μm inclusive.

5. (Twice Amended) A method of fabricating a display device comprising the steps of:

forming a semiconductor film over a substrate;

forming a gate insulating film on the semiconductor film;

forming a gate wiring on the gate insulating film;

forming a first organic leveling film over the gate wiring;

forming a second organic leveling film on the first organic leveling film; and

forming a pixel electrode on the second organic leveling film,

wherein the thickness of the first organic leveling film is thinner than that of the second organic leveling film, and

wherein the first organic leveling film and the second organic leveling film are insulating films formed by spin coating.

6. (Twice Amended) A method of fabricating a display device comprising the steps of:

forming a semiconductor film over a substrate;

forming a gate insulating film on the semiconductor film;

forming a gate wiring on the gate insulating film;

forming a first organic leveling film over the gate wiring;

forming a second organic leveling film on the first organic leveling film; and
forming a pixel electrode on the second organic leveling film,
wherein the thickness of the first organic leveling film is thinner than that of the second
organic leveling film, and

wherein each of the first organic leveling film and the second organic leveling film comprises
at least one of a polyimide resin and an acrylic resin.

7. (Twice Amended) A method of fabricating a display device comprising the steps of:

forming a semiconductor film over a substrate;
forming a gate insulating film on the semiconductor film;
forming a gate wiring on the gate insulating film;
forming a first organic leveling film over the gate wiring;
forming a second organic leveling film on the first organic leveling film; and
forming a pixel electrode on the second organic leveling film,
wherein the thickness of the first organic leveling film is thinner than that of the second
organic leveling film, and

wherein the first organic leveling film and the second organic leveling film comprise the same
material.

8. (Amended) A method of fabricating a display device comprising the steps of:

forming a semiconductor film over a substrate;
forming a gate insulating film on the semiconductor film;

forming a gate wiring on the gate insulating film;
forming a first organic leveling film comprising resin over the gate wiring;
forming a second organic leveling film comprising resin on the first organic leveling film; and
forming a pixel electrode on the second organic leveling film,
wherein the thickness of the first organic leveling film is thinner than that of the second organic leveling film.

9. (Amended) A method of fabricating a display device comprising the steps of:
forming a semiconductor film over a substrate;
forming a gate insulating film on the semiconductor film;
forming a gate wiring on the gate insulating film;
forming a insulating film comprising an inorganic material over the gate insulating film;
forming a first organic leveling film over the insulating film;
forming a second organic leveling film on the first organic leveling film; and
forming a pixel electrode on the second organic leveling film,
wherein the thickness of the first organic leveling film is thinner than that of the second organic leveling film.

10. (Amended) A method of fabricating a display device comprising the steps of:
forming a semiconductor film over a substrate;
forming a gate insulating film on the semiconductor film;
forming a gate wiring on the gate insulating film;

applying a first organic layer comprising resin by spin coating;
baking the first organic layer to form a first organic leveling film;
applying a second organic layer comprising resin by spin coating;
baking the second organic layer to form a second organic leveling film; and
forming a pixel electrode on the second organic leveling film,
wherein the thickness of the first organic leveling film is thinner than that of the second
organic leveling film.

11. (Amended) A method according to claim 1, wherein the display device is a liquid crystal
display device or an EL display device.

12. (Amended) A method according to claim 1, wherein the display device is used in one
selected from the group consisting of a portable phone, a video camera, a computer, and a projector.

13. (Amended) A method according to claim 2, wherein the display device is a liquid crystal
display device or an EL display device.

14. (Amended) A method according to claim 2, wherein the display device is used in one
selected from the group consisting of a portable phone, a video camera, a computer, and a projector.

15. (Amended) A method according to claim 3, wherein the display device is a liquid crystal
display device or an EL display device.

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16. (Amended) A method according to claim 3, wherein the display device is used in one selected from the group consisting of a portable phone, a video camera, a computer, and a projector.

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17. (Amended) A method according to claim 4, wherein the display device is a liquid crystal display device or an EL display device.

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18. (Amended) A method according to claim 4, wherein the display device is used in one selected from the group consisting of a portable phone, a video camera, a computer, and a projector.

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19. (Amended) A method according to claim 5, wherein the display device is a liquid crystal display device or an EL display device.

20. (Amended) A method according to claim 5, wherein the display device is used in one selected from the group consisting of a portable phone, a video camera, a computer, and a projector.

21. (Amended) A method according to claim 6, wherein the display device is a liquid crystal display device or an EL display device.

22. (Amended) A method according to claim 6, wherein the display device is used in one selected from the group consisting of a portable phone, a video camera, a computer, and a projector.

23. (Amended) A method according to claim 7, wherein the display device is a liquid crystal display device or an EL display device.

24. (Amended) A method according to claim 7, wherein the display device is used in one selected from the group consisting of a portable phone, a video camera, a computer, and a projector.

25. (Amended) A method according to claim 8, wherein the display device is a liquid crystal display device or an EL display device.

26. (Amended) A method according to claim 8, wherein the display device is used in one selected from the group consisting of a portable phone, a video camera, a computer, and a projector.

27. (Amended) A method according to claim 9, wherein the display device is a liquid crystal display device or an EL display device.

28. (Amended) A method according to claim 9, wherein the display device is used in one selected from the group consisting of a portable phone, a video camera, a computer, and a projector.

29. (Amended) A method according to claim 10, wherein the display device is a liquid crystal display device or an EL display device.